

ICSICT-2018 Participation Report

EMI Reduction and Output Ripple Improvement of Switching DC-DC Converters with Linear Swept Frequency Modulation



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ACKNOWLEDGEMENT

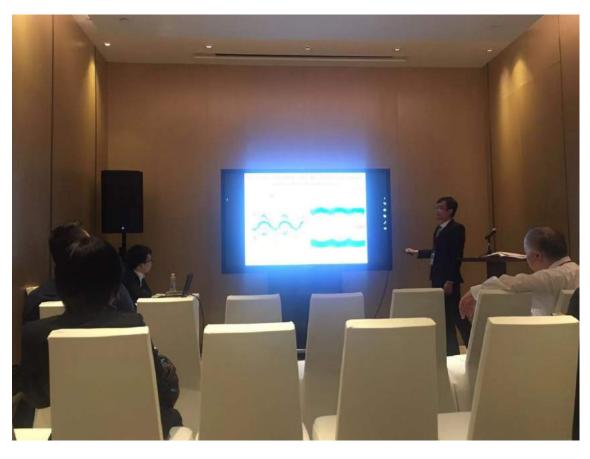
I would like to thank Prof. H. Kobayashi, Dr. Kobori and Kobayashi Lab members who gave me a good chance to travel many beautiful places at Qingdao in China.







I would like to thank my lovely Prof. Kobayashi!



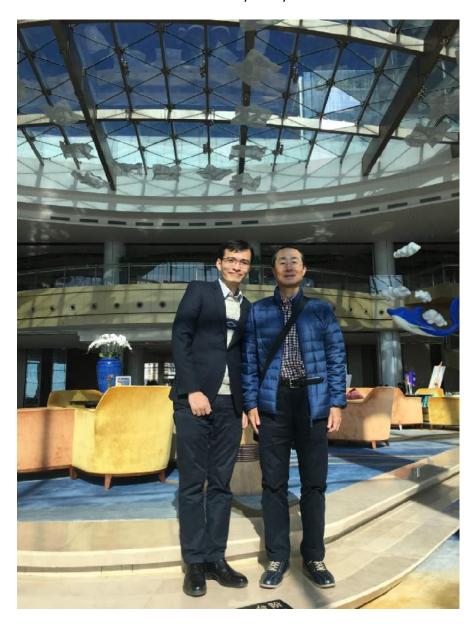
It was the first time I attended a large conference, therefore I was very nervous.

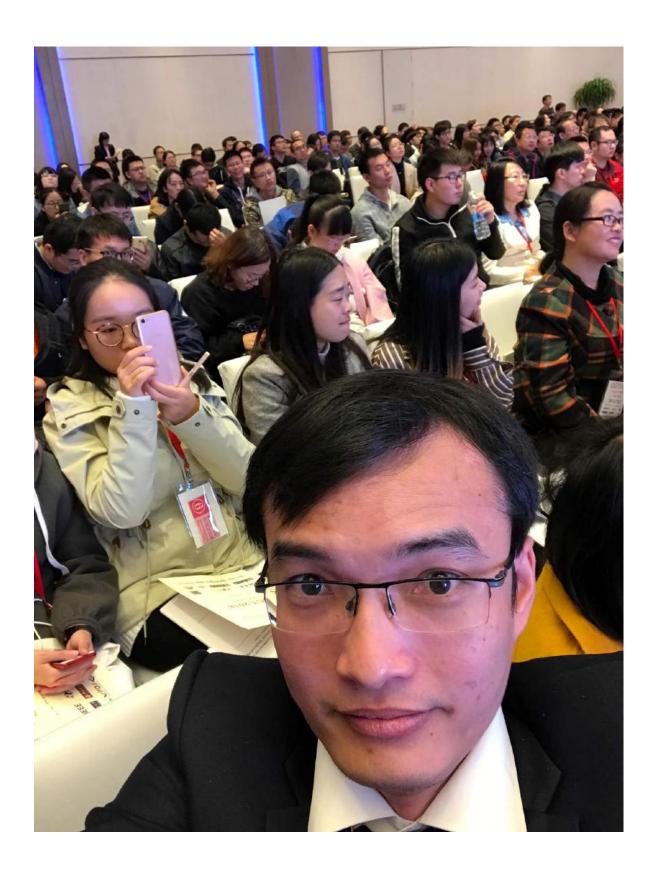


I would like to thank my lovely Dr. Kobori!



I would like to thank my lovely Dr. Mastuda!







I would like to thank Prof. Thomas Skotnicki!

https://www.semiwiki.com/forum/content/4830-thomas-skotnicki-fd-soi-26-years-making.html

In one particular instance, Thomas had a long fight over a key paper at IEEE Transactions on Electron Devices, where the editors didn't want to publish. Then a serendipitous change of editor opened the door to publication; the paper was given the Rappaport Award, as "best publication of the year" by the IEEE Electron Devices Society. As Mahatma Gandhi said: First they ignore you, then they laugh at you, then they fight you, then you win.

With these successes building momentum, the semiconductor community finally started to believe in the idea. One important believer was Carlos Mazure from SOITEC where they make wafer blanks. SOITEC was excited by the potential of these thin-box, short-channel devices, but at the time they could only make a box 145nm thick, not the 10-20nm that was required. Under Carlos' leadership, SOITEC was instrumental in launching the R&D program that successfully delivered thin box SOI wafers.

At this point LETI got involved. Although most of their work was on thick-box devices, they decided to collaborate with Thomas to actually fabricate his ideas into real silicon. LETI helped with both silicon-onnothing and then with thin-box FD-SOI. Up until then it had all been equations. The whole idea gained speed once the project was transferred from the whiteboard to silicon.

Then, in 2011, Intel announced FinFET. Everyone already knew about FinFET and it was known to be really difficult technology. The complexity of FinFETs and the concerns about efficiently producing it led to raucous debate within the industry and within companies. Thomas sold the deal at ST when he showed that by turning a FinFET on its side you pretty much had silicon-on-nothing, FD-SOI with a thin box. It was the biggest day of Thomas' professional life when ST's top management, including CEO Carlo Bozotti, COO Jean-Marc Chery, and EVP of Front-End Manufacturing Joël Hartmann made the decision to take its Ultra-Thin Body and Box FD-SOI to manufacture. Thomas recounted that from initial conception and equations to industrial fabrication it took 26 years.

Industrialization of the manufacturing process went fast since the technology worked even better than the equations and FD-SOI is a much simpler technology than FinFET—it leverages the learnings of planar (bulk) silicon with fewer masks and processing steps, albeit with a slightly more expensive wafer.



Still, selling FD-SOI beyond ST took a bit more time, as initially ST was alone and customers require partners, second sources, alliances and not just a single manufacturer. Today, however, the technology is being deployed worldwide not just at ST but also at Samsung and GlobalFoundries.

As a marketing guy, I can't but help noticing a missed opportunity. "Silicon on nothing" is a much better name than FD-SOI.



I would like to thank Prof. Adrian Ionescu!

https://people.epfl.ch/cgi-bin/people?id=122431&lang=en&cvlang=en

EPFL > People@EPFL > Mihai Adrian Ionescu

français / English

MIHAI ADRIAN IONESCU

Contact Biography & current work Main publications Teaching & PhD

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Biography and current work

Mission

The Nanoelectronic Devices group (NANOLAB) is working on various subjects in the field of silicon micro/nanoelectronics with special emphasis on the technology, design and modelling of nanoscale solid-state devices (including Silicon-On-Insulator devices, few-electron devices, hybrid SET/CMOS, single electron memory, rianowires and nanotubes), Radio Frequency MEMS devices for in- and above-IC and integrated optoelectronic

The group is interested in exploring new materials, novel fabrication techniques, and novel device concepts for future nanoelectronic systems.

Biography

Adrian M. Ionescu is Full Professor at the Swiss Federal Institute of Technology, Lausanne, Switzerland. He received the B.S./M.S. and Ph.D. degrees from the Polytechnic Institute of Bucharest, Romania and the National Polytechnic Institute of Grenoble, France, in 1989 and 1997, respectively. He has held staff and/or visiting positions at LETI-CEA, Grenoble, France and INP Grenoble, France and Stanford University, USA, in 1998 and 1999

Dr. Ionescu has published more than 400 articles in international journals and conferences. He received many Best Paper Awards in international conferences, the Annual Award of the Technical Section of the Romanian Academy of Sciences in 1994 and the Blondel Medal in 2009 for remarkable contributions to the progress in engineering sciences in the domain of electronics. He is the 2013 recipient of the IBM Faculty Award in Engineering. He served the IEDM and VLSI conference technical committees and was the Technical Program Committee (Co)Chair of ESSDERC in 2006 and 2013

He is director of the Laboratory of Micro/Nanoelectronic Devices (NANOLAB). He is appointed as national representative of Switzerland for the European Nanoelectronics Initiative Advisory Council (ENIAC) and member of the Scientific Committee of CATRENE. Dr. Ionescu is the European Chapter Chair of the ITRS Emerging Research Devices Working Group.





FIELDS OF EXPERTISE

Nanoelectronic devices Silicon nanotechnology Silicon On Insulator Radio Frequency MEMS and NEMS Small Swing Switches **Emerging Memories** Modeling and Simulation of Solid-State Electronic



I would like to thank Prof. Yeo Kiat Seng!

https://epd.sutd.edu.sg/people/faculty/yeo-kiat-seng

Yeo Kiat Seng

Associate Provost, Research & International Relations

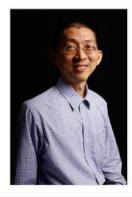
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Research Areas:

Electrical Engineering

Pillar / Cluster: Engineering Product Development



Biography

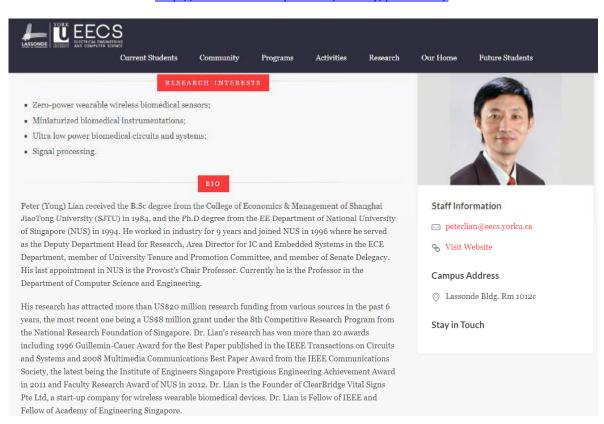
Associate Provost for International Relations and Graduate Studies, Professor Yeo Klat-Seng Joined Singapore University of Technology and Design (SUTD) on 2nd July 2014. He has over 25 years of experience in industry, academia and consultancy. Before his appointment at SUTD, he was Full Professor at Nanyang Technological University (NTU), Singapore, and spent 13 years in management positions as associate Chair (Research), Head of Circuits and Systems and Sub-Dean (Student Affairs) in the School of Electrical and Electronic Engineering (EEE). As Associate Chair (Research), he developed EEE mega research enteries into a top-notch hub to advance cutting-edge research innovations and unparalleled inventions. Prof. Yeo was also a Fellow of the Renaissance Engineering Programme (REP) and served as Senator and Advisory Board Member at NTU. Besides, he was the Founding Director of ViRTUS, a 5550 million IC Design Centre of Excellence Jointly set up by NTU and Singapore Economic Development Board. Since 1996, he has been providing consultancy services to statutory boards, local SHES and multinational corporations in the areas of electronics and IC designs.

Currently, Prof. Yeo Is a Visiting Professor in the School of EEE at NTU, a Member of Board of Advisors of the Singapore Semiconductor Industry Association, a Council Member of the Assembly & Test WSQ Framework Industry Skills and Training of the Singapore Workforce Development Agency, a Member of the Engineering Science (ES) Advisory Committee of Ngee Ann Polytechnic and a Member of Hwa Chong Institutional IP Advisory Board.



I would like to thank Prof. Yong Lian!

http://eecs.lassonde.yorku.ca/faculty/peter-lian/





I would like to thank Prof. Cheng Yuhua!

http://eecs.pku.edu.cn/EN/People/Faculty/Detail/?ID=5954



Cheng, Yuhua

Professor

Research Interests: Advanced analog/mixed-signal/RF integrated circuits for system integration applications

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Cheng, Yuhua received the BSEE, MSEE, and Ph.D. EE degrees in Shandong Polytechnic University (Now Shandong University), Tianjin University, and Tsinghua University, China in 1982, 1985 and 1989, respectively. In 1990, he joined in the Institute of Microelectronics (IME), Peking University, China, From 1992 to 1996, he was an associate professor in IME. He is now with Peking University, as a full professor.

Dr. Cheng has served on many Technical Program Committees and chaired numerous Sub-committees at international conferences, including the IEEE Custom Integrated Circuits Conference (CICC) (from 2002 to 2005) and Radio Frequency Integrated Circuits Symposium (since 2002). He organized and participated in numerous workshops and panels related to RFCMOS technology and SoC design. He has authored and co-authored over 160 research papers, two book chapters, two books "MOSFET Modeling & BSIM3 User's Guide" by Kluwer Academic Publishers (1999), and "Device modeling for analog/RF circuit design" by John Wiley and Sons (2002). He was a Guest Editor for IEEE Journal of Solid-State Circuits. He is an IEEE Fellow and a member of both Electronic Device Society (EDS) and Solid-state Circuit Society (SCS). His research interests include smart power discrete semiconductor devices and advanced analog/mixed-signal/RF integrated circuits for system integration applications.

Dr.Cheng was the principal developer to BSIM3v3 (Yuhua Cheng, et al., BSIM3v3 User's Manual, UC Berkeley, UCB/ERL M97/2, 1997). Due to Dr. Cheng's efforts, the discontinuity problems, considered as a major shortcoming in BSIM models, were resolved in BSIM3v3, while many new physical effects were implemented. BSIM3v3 has been used worldwide by foundries and design companies for IC simulation. It was selected as the first MOSFET model for compact model standardization effort for IC simulation by Electronics Industry Association/Compact Model Council and given an R&D 100 Award in 1996.

Since 2006, Dr. Cheng has been conducting research on ESD for more than 10 years, which has made significant achievements, which resulted in more than 30 research papers. He shared with the IC industry his research results in international conferences and journals including IEEE Journal of Solid-state Circuits, IEEE Trans. On Electron Devices, and IEEE Electron Devices Letters.



I would like to respect, thank and acknowledge the ICSICT 2018 which gave me a chance to represent my research paper.



I would like to thank my new friend!



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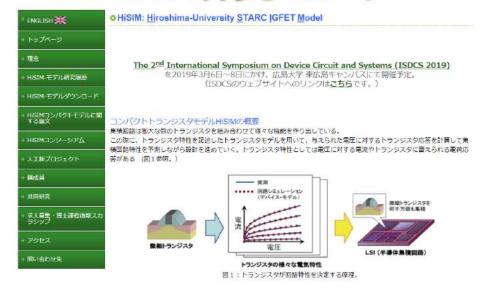
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https://www.hisim.hiroshima-u.ac.jp/

HiSIM 研究センター









谢谢

Don't be sad my friend!

I hope that you will be able to come back Qingdao on someday in future!

